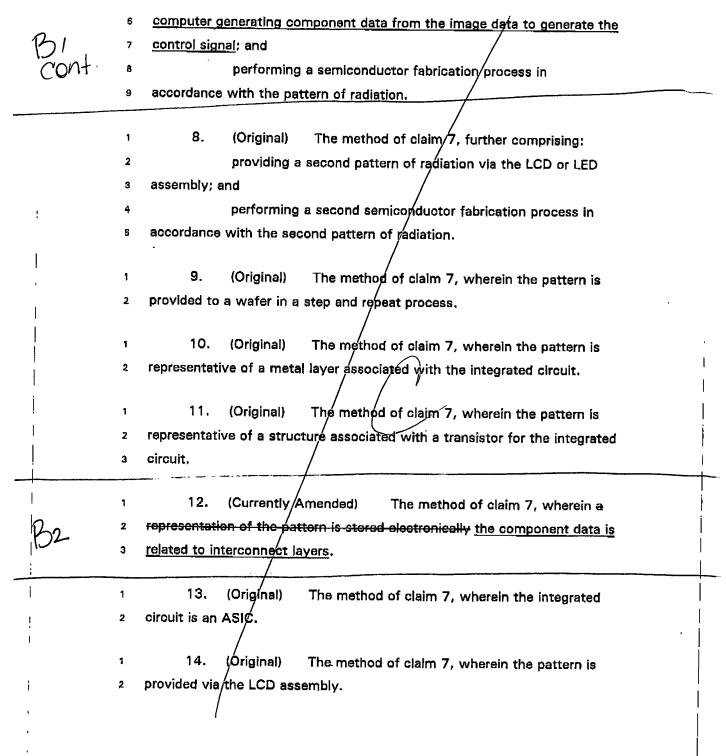
Atty. Dkt. No. 039153-0306 (F0793)

1. (Cancelled) A lithographic system for/an integrated circuit fabrication process, the lithographic system comprising: 2 3 a computer; and 4 a configurable mask or reticle coupled to the computer, wherein the configurable mask or reticle allows light to be transmitted in a 6 pattern controlled by a control signal from the computer. 6 2. (Cancelled) The lithographic system of claim 1, wherein the 1 configurable mask or reticle is an LCD or LED matrix. 2 3. (Cancelled) The lithographic system of claim 1 further comprising: 2 3 a database for providing image information associated with a device to be patterned on a wafer, the computer using the image 4 information to generate the control signal. 5 4. (Cancelled) The lithographic system of claim 3, wherein the database is stored on/a storage mediá. 2 5. 1 (Cancelled) The lithographic system of claim 3, wherein the image information is related to transistor structures. 2 6. (Cancelled) The lithographic system of claim 1, wherein the 1 control signal is, a video signal. 2 7, 1 (Currently Amended) A method of manufacturing an integrated circuit, the method comprising: 2 3 providing a pattern of radiation via an LCD or LED assembly 4 in response tola control signal from a computer, the computer generating

the control signal in response to image data stored in a database, the

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15. (Cancelled) A pattern generator for an integrated circuit fabrication system, the pattern generator comprising: 2 means for providing a pattern of light; and 3 means for controlling the means for providing, wherein the 5 means for controlling selects the pattern. (Cancelled) The pattern generator of claim 15, further 1 16, 2 comprising: 3 means for providing a light through the means for providing a pattern. 1 17, (Cancelled) The pattern generator of claim 16, further 2 comprising: Э means for focusing the light on a wafer. 18. (Cancelled) The pattern generator of claim 15, further 1 comprising: 2 3 means for storing elements, wherein the means for controlling creates a control signal representative of the pattern in 4 response to the elements/ 5 1 19. (Cancelled) The pattern generator of claim 15, wherein the means for controlling includes a workstation executing a software 2 3 program.

Please add the following new claims 21-32:

means for providing a pattern includes liquid crystals.

(Cancelled) The pattern generator of claim 19, wherein the

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20.

- 1 21. (New) A method of using a pattern generator, for an integrated circuit fabrication system, the method comprising: 2 providing a pattern of radiation via an LÇD assembly in response to a control signal from a computer, the computer generating the 4 control signal in response to image data stored in/a database, the 5 computer generating component data from the image data to generate the 6 control signal; and 7 performing a semiconductor fabrication process in 8 accordance with the pattern of radiation. 9
- 22. (New) The method of claim 21, wherein the pattern is for an ASIC device.
- 1 23. (New) The method of claim 22, wherein in the pattern
 2 generator further comprises:
 3 means for providing a pattern of light;
- means for controlling the means for providing, wherein the
 means for controlling selects the pattern; and
 means for focusing the light on a wafer.
- 1 24. (New) The method of claim 15, wherein the image data are shapes representing component interconnects.
- 1 25. (New) The method of claim 23, wherein the means for controlling includes a workstation executing a software program.
- 26. (New) The method of claim 25, wherein the means for providing a pattern includes liquid crystals.

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27. (New) In a lithographic system for an integrated circuit fabrication process, the lithographic system including a computer and a 2 configurable mask or reticle coupled to the computer, wherein the 3 configurable mask or reticle allows light to be/transmitted in a pattern controlled by a control signal from the computer, a method comprising: 5 6 providing a pattern of radiation via the configurable mask or reticle in response to a control signal from a computer, the computer 7 В generating the control signal in response to image data stored in a database, the computer using component data from the image data to 9 generate the control signal; and 10 performing a semiçonductor fabrication process in 17 accordance with the pattern of radiation. 12

Cont

- 28. (New) The method of claim 27, wherein the configurable mask or reticle is an LCD or LED matrix.
- 1 29. (New) The method of claim 27 wherein the image data 2 includes ASIC information.
- 1 30. (New) The method of claim 29, wherein the database is 2 stored on a storage media.
- 1 31. (New) The method of claim 27, wherein the image data is 2 related to transistor structures.
- 1 32./ (New) The method of claim 27, wherein the control signal is 2 a video signal.